## BAE SYSTEMS

# 32K x 8 Radiation Hardened Static RAM – 5 V

167A690 182A934

#### **Features**

## **Product Description**

#### Radiation

- Fabricated with Bulk CMOS 0.8 µm Process
- Total Dose Hardness through 1x10<sup>6</sup> rad(Si)
- Neutron Hardness through 1x10<sup>14</sup> N/cm<sup>2</sup>
- Dynamic and Static Transient Upset Hardness through 1x10<sup>9</sup> rad(Si)/s
- Soft Error Rate of < 1x10<sup>-11</sup> Upsets/Bit-Day
- Dose Rate Survivability through 1x10<sup>12</sup> rad(Si)/s
- Latchup Free

#### Other

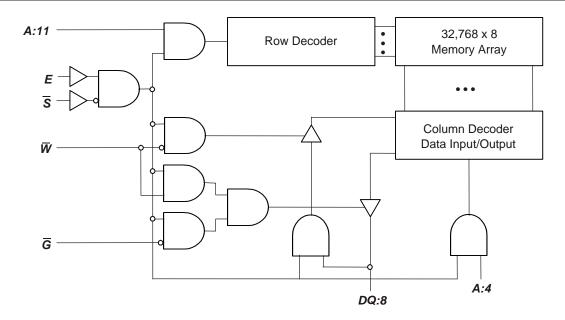
- Read/Write Cycle Times ≤30 ns (-55 °C to 125°C)
- SMD Number 5962H92153
- · Asynchronous Operation
- CMOS or TTL Compatible I/O
- Single 5 V ±10% Power Supply
- · Low Operating Power
- · Packaging Options
  - 36-Lead Flat Pack (0.630" x 0.650")
  - 28-Lead DIP, MIL-STD-1835, CDIP2-T28

#### General Description

The 32K x 8 radiation hardened static RAM is a high performance, low power device designed and fabricated in 0.8 µm Radiation Hardened Complementary Metal Oxide Semiconductor (RHCMOS) technology. BAE SYSTEMS' device is designed for radiation environments using industry standard functionality. The memory can be personalized for either CMOS or Transistor Transistor Logic (TTL) input receivers. The SRAM operates over the full military temperature range and requires a single 5 V ±10% power supply. Power consumption is typically less than 20 mW/MHz in operation, and less than 10 mW in the low power disabled mode. The SRAM read operation is fully asynchronous, with an associated typical access time of 20 nanoseconds.

BAE SYSTEMS' bulk CMOS technology achieves radiation hardening via a combination of process technology enhancements and specific circuit improvements.





## Signal Definitions

- A: 0-14 Address input pins that select a particular eight-bit word within the memory array.
- DQ: 0-7 Bi-directional data pins that serve as data outputs during a read operation and as data inputs during a write operation.
  - Negative chip select, when at a low level, allows normal read or write operation. When at a high level, so forces the SRAM to a precharge condition, holds the data output drivers in a high impedance state and disables the data input buffers only. If this signal is not used, it must be connected to GND.
- Negative write enable, when at a low level, activates a write operation and holds the data output drivers in a high impedance state. When at a high level, W allows normal read operation.
- Regative output enable, when at a high level holds the data output drivers in a high impedance state. When at a low level, the data output driver state is defined by S, W, and E. If this signal is not used it must be connected to GND.
- Chip enable, when at a high level allows normal operation. When at a low level, E forces the SRAM to a precharge condition, holds the data output drivers in a high impedance state and disables all the input buffers except the S input buffer. If this signal is not used, it must be connected to V<sub>DD</sub>.

#### Truth Table

Mode			Inputs <sup>(1)</sup>	,(2)		Dawer
Mode	E (4)	s	W	G	1/0	Power
Write	High	Low	Low	Х	Data-In	Active
Read	High	Low	High	Low	Data-Out	Active
Standby	Χ	High	X	Х	High-Z	Standby
Standby <sup>(3)</sup>	Low	Х	Х	Х	High-Z	Standby

#### Notes:

- 1)  $V_{IN}$  for don't care (X) inputs =  $V_{II}$  or  $V_{IH}$ .
- 2) When  $\overline{G} = high$ , I/O is high-Z.
- 3) To dissipate the minimum amount of standby power when in standby mode:  $\overline{S} = V_{DD}$  and E = GND. All other input levels may float.
- 4) E is tied high internally to the chip for the 28-DIP package.

Applied Conditions <sup>(1)</sup>	Minimum	Maximum
Storage Temperature Range (Ambient)	-65°C	+150°C
Operating Temperature Range (T <sub>CASE</sub> )	-55°C	+125°C
Positive Supply Voltage	-0.5 V	+7.0 V
Input Voltage <sup>(2)</sup>	-0.5 V	V <sub>DD</sub> + 0.5 V
Output Voltage <sup>(2)</sup>	-0.5 V	V <sub>DD</sub> + 0.5 V
Power Dissipation <sup>(3)</sup>		2.0 W
Lead Temperature (Soldering 5 sec)		+250°C
Electrostatic Discharge Sensitivity <sup>(4)</sup>	(Clas	s II)

#### Notes:

- 1) Stresses above the absolute maximum rating may cause permanent damage to the device. Extended operation at the maximum levels may degrade performance and affect reliability. All voltages are with reference to the module ground leads.
- 2) Maximum applied voltage shall not exceed +7.0 V.
- 3) Guaranteed by design; not tested.
- 4) Class as defined in MIL-STD-883, Method 3015.

## **Recommended Operating Conditions**

Symbol	Parameters <sup>(1)</sup>	Minimum	Maximum	Units
$V_{DD}$	Supply Voltage	+4.5	+5.5	Volt
GND	Supply Voltage Reference	0.0	0.0	Volt
$T_C$	Case Temperature	-55	+125	Celsius
V	Input Logic "Low" - CMOS	0.0	+1.5	Volt
$V_{IL}$	Input Logic "Low" - TTL	0.0	+0.8	VOIL
$V_{IH}$	Input Logic "High" - CMOS	+3.5	$V_{DD}$	Volt
▼IH	Input Logic "High" - TTL	+2.0	$V_{DD}$	VOIL

#### Note:

1)All voltages referenced to GND.

## **Power Sequencing**

The substrate of this module is connected directly to Ground. Power shall be applied to the device only in the following sequences to prevent damage due to excessive currents:

Power-Up Sequence: GND, V<sub>DD</sub>, Inputs
 Power-Down Sequence: Inputs, V<sub>DD</sub>, GND

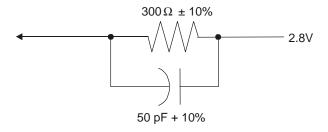
## **DC Electrical Characteristics**

Toot	Symbol	Took Conditions(1)	Device Type	Lin	nits	Unito
Test	Syllibol	Test Conditions <sup>(1)</sup>	Device Type	Minimum	Maximum	Units
Supply Current	I <sub>DD1</sub>	$\frac{F}{S} = F_{MAX} = 1/t_{AVAV(min)}$ $\frac{F}{S} = V_{IL} = GND$	X3X		180	mA
(Cycling Selected)	1טטי	E = V <sub>IH</sub> = V <sub>DD</sub> No Output Load	X4X X6X		130	mA
Supply Current		$F = F_{MAX} = 1/t_{AVAV(min)}$	X3X		2.0	mA
(Cycling De-Selected)	$I_{DD2}$	$\overline{S} = V_{IH} = V_{DD}$	X4X		1.2	mA
(Gyolling De Gelected)		E = V <sub>IL</sub> = GND	X6X		2.0	mA
0		$F = F_{MAX} = 1/t_{AVAV(min)}$	X3X		2.0	mA
Supply Current	$I_{DD3}$	$\overline{S} = V_{IH} = V_{DD}$	X4X		1.2	mA
(Standby)	220	$E = V_{IL} = GND$	X6X		2.0	mA
			X3X		1.0	mA
Data Retention Current	$I_{DR}$	$V_{DD} = 2.5 \text{ V}$	X4X		0.4	mA
			X6X		1.0	mA
	1/	I <sub>OH</sub> = -4 mA	A.II	4.2		
High Level Output Voltage	V <sub>OH</sub>	I <sub>OH</sub> = -200 μA	All	V <sub>DD</sub> - 0.5 V		V
Low Lovel Output Voltage	\/	I <sub>OL</sub> = 8 mA	All		0.4	V
Low Level Output Voltage	$V_{OL}$	I <sub>OL</sub> = 200 μA	All		0.05	V
Data Retention Voltage	$V_{DR}$	$V_{DD} = V_{DR}$	All	2.5		V
High Level Input Voltage	$V_{IH}$		CMOS	3.5		V
riigii Lovoi iiiput voitago	VIН		TTL	2.0		V
Low Level Input Voltage	$V_{IL}$		CMOS		1.5	V
Low Level Input Voltage	۷IL		TTL		0.8	V
Input Leakage	$I_{ILK}$	$0 \text{ V} \leq V_{IN} \leq 5.5 \text{ V}$	All	-5	5	μΑ
Output Leakage	I <sub>OLK</sub>	$0 \text{ V} \le \text{V}_{\text{OUT}} \le 5.5 \text{ V}$	All	-10	10	μΑ
C <sub>in</sub>	(2)	By Design/ Verified By Characterization	All		4	pF
C <sub>out</sub>	(2)	By Design/ Verified By Characterization	All		7	pF

#### Note:

- 1) Typical operating conditions:  $V_{DD} = 5.0V$ ; TA = 25 °C, pre-radiation. -55°C £  $T_{case}$  £ +125°C; 4.5 V £  $V_{DD}$  £ 5.5 V; unless otherwise specified. 2) The worst case timing sequence of  $t_{WLZQ} + t_{DUWH} + t_{WHWL} = t_{AVAV}$ .

## **Output Load Circuit**

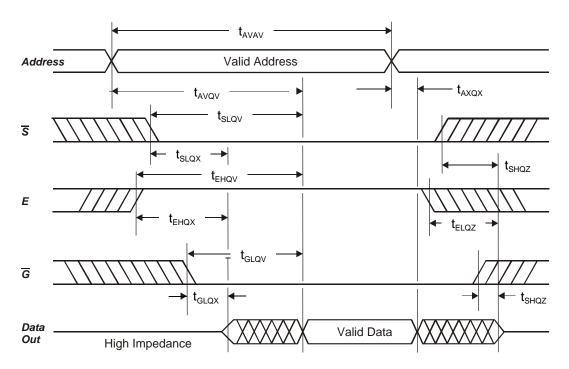


Tark	0	Symbol Minimum or Worst Case By Speed			ed	Unite
Test	Symbol	Maximum	-30	-40	-60	Units
Read Cycle Time	t <sub>AVAV</sub>	Minimum	30	40	60	ns
Address Access Time	t <sub>AVQV</sub>	Maximum	30	40	60	ns
Output Hold After Address Change	t <sub>AXQX</sub>	Minimum	5	5	5	ns
Chip Select Access Time	t <sub>SLQV</sub>	Maximum	30	40	60	ns
Chip Select to Output Active	t <sub>SLQX</sub>	Minimum	3	3	3	ns
Chip Select to Output Disable	t <sub>SHQZ</sub>	Maximum	CMOS - 10 TTL - 12	15	15	ns
Chip Enable Access Time	$t_{EHQV}$	Maximum	30	40	60	ns
Chip Enable to Output Active	t <sub>EHQX</sub>	Minimum	3	3	3	ns
Chip Disable to Output Disable	t <sub>ELQZ</sub>	Maximum	CMOS - 10 TTL - 12	. 15	15	ns
Output Enable Access Time	t <sub>GLQV</sub>	Maximum	CMOS - 12 TTL - 15	CMOS - 15 TTL - 18	15	ns
Output Enable to Output Active	t <sub>GLQX</sub>	Minimum	3	3	3	ns
Output Enable to Output Disable	t <sub>GHQZ</sub>	Maximum	CMOS - 10 TTL - 12	15	15	ns

#### Note:

1)Test conditions: input switching levels  $V_{IL}/V_{IH} = 0.5 \text{ V/V}_{DD}$  -0.5 V (CMOS),  $V_{IL}/V_{IH} = 0 \text{ V/3 V}$  (TTL), input rise and fall times < 5 ns, input and output timing reference levels shown in the Tester AC Timing Characteristics table, capacitive output loading  $C_L = 50 \text{ pF}$ . For  $C_L > 50 \text{ pF}$ , derate access times by 0.02 ns/pF (typical). -55 °C £  $T_{case}$  £ +125°C; 4.5 V £  $V_{DD}$  £ 5.5 V; unless otherwise specified.

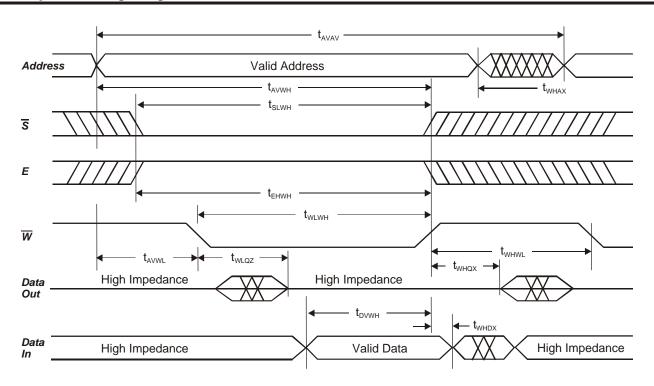
## Read Cycle Timing Diagram



Test	Symbol		Wors	t Case By	Units	
rest	Syllibol	Maximum	-30	-40	-60	Units
Write Cycle Time	t <sub>AVAV</sub>	Minimum	35	40	40	ns
Write Pulse Width	$t_{WLWH}$	Minimum	30	35	55	ns
Chip Select to End of Write	t <sub>SLWH</sub>	Minimum	30	35	55	ns
Data Setup to End of Write	t <sub>DVWH</sub>	Minimum	25	30	40	ns
Address Setup to End of Write	t <sub>AVWH</sub>	Minimum	30	35	55	ns
Data Hold After End of Write	t <sub>WHDX</sub>	Minimum	3	3	5	ns
Address Setup to Start of Write	t <sub>AVWL</sub>	Minimum	0	0	0	ns
Address Hold After End of Write	t <sub>WHAX</sub>	Minimum	0	0	0	ns
Write Enable to Output Disable	t <sub>WLQZ</sub>	Maximum	12	15	15	ns
Output Active After End of Write	t <sub>WHQX</sub>	Minimum	1	1	3	ns
Write Pulse Width Access Time	t <sub>WHWL</sub>	Minimum	5	5	5	ns
Chip Enable to End of Write	t <sub>EHWH</sub>	Minimum	30	35	55	ns
Address Hold After End of Write	t <sub>ELWH</sub>	Minimum	0	0	0	ns

#### Note:

## Write Cycle Timing Diagram



<sup>1)</sup> Test conditions: input switching levels  $V_{IL}/V_{IH} = 0.5 \text{ V/V}_{DD}$  - 0.5 V (CMOS),  $V_{IL}/V_{IH} = 0 \text{ V/3 V}$  (TTL), input rise and fall times < 5 ns, input and output timing reference levels shown in the Tester AC Timing Characteristics table, capacitive output loading = 50 pF. -55°C £  $T_{case}$  £ +125°C; 4.5 V £  $V_{DD}$  £ 5.5 V; unless otherwise specified.

### **Dynamic Electrical Characteristics**

#### Read Cycle

The RAM is asynchronous in operation, allowing the read cycle to be controlled by address, chip select  $(\overline{S})$ , or chip enable (E) (refer to Read Cycle Timing diagram). To perform a valid read operation, both chip select and output enable  $(\overline{G})$  must be low and chip enable and write enable  $(\overline{W})$  must be high. The output drivers can be controlled independently by the  $\overline{G}$  signal. Consecutive read cycles can be executed with  $\overline{S}$  held continuously low, and with  $\overline{S}$  held continuously low, and with  $\overline{S}$  held continuously high, and toggling the addresses.

For an address-activated read cycle,  $\overline{S}$  and E must be valid prior to or coincident with the activating address edge transition(s). Any amount of toggling or skew between address edge transitions is permissible; however, data outputs will become valid  $t_{AVQV}$  time following the latest occurring address edge transition. The minimum address activated read cycle time is  $t_{AVQV}$ . When the RAM is operated at the minimum address-activated read cycle time, the data outputs will remain valid on the RAM I/O until  $t_{AXQX}$  time following the next sequential address transition.

To control a read cycle with  $\overline{S}$ , all addresses and E must be valid prior to or coincident with the enabling  $\overline{S}$  edge transition. Address or E edge transitions can occur later than the specified setup times to  $\overline{S}$ ; however, the valid data access time will be delayed. Any address edge transition, that occurs during the time when  $\overline{S}$  is low, will initiate a new read access, and data outputs will not become valid until tayout time following the address edge transition. Data outputs will enter a high impedance state  $t_{SHQZ}$  time following a disabling  $\overline{S}$  edge transition.

To control a read cycle with E, all addresses and  $\overline{S}$  must be valid prior to or coincident with the enabling E edge transition. Address or  $\overline{S}$  edge transitions can occur later than the specified setup times to E; however, the valid data access time will be delayed. Any address edge transition that occurs during the time when E is high will initiate a new read access, and data outputs will not become valid until  $t_{AVQV}$  time following the address edge transition. Data outputs will enter a high impedance state  $t_{ELQZ}$  time following a disabling E edge transition.

#### Write Cycle

The write operation is synchronous with respect to the address bits, and control is governed by write enable  $(\overline{W})$ , chip select  $(\overline{S})$ , or chip enable (E) edge transitions (refer to Write Cycle Timing diagrams). To perform a write operation, both  $\overline{W}$  and  $\overline{S}$  must be low, and E must be high. Consecutive write cycles can be performed with  $\overline{W}$  or  $\overline{S}$  held continuously low, or E held continuously high. At least one of the control signals must transition to the opposite state between consecutive write operations.

The write mode <u>can</u> be controlled via three different control signals: W, S, and E. All three modes of control are similar except the S and E controlled modes actually disable the RAM during the write recovery pulse. Only the W controlled mode is shown in the table and diagram on the previous page for simplicity. However, each mode of control provides the same write cycle timing characteristics. Thus, some of the parameter names referenced below are not shown in the write cycle table or diagram, but indicate which control pin is in control as it switches high or low.

To write data into the RAM, W and S must be held low and E must be held high for at least  $t_{\mbox{\tiny NLWH}}/t_{\mbox{\tiny SLSH}}/t_{\mbox{\tiny EHEL}}$  time. Any amount of edge skew between the signals can be tolerated and any one of the control signals can initiate or terminate the write operation. For consecutive write operations, write pulses must be separated by the minimum specified  $t_{WHWL}/t_{SHSL}/t_{ELEH}$  time. Address inputs must be  $\underline{\text{valid}}$  at least  $t_{\text{\tiny AVWL}}/t_{\text{\tiny AVSL}}/t_{\text{\tiny AVEH}}$  time before the enabling W/S/E edge transition, and must remain valid during the entire write time. A valid data overlap of write pulse width time of  $t_{DVWH}/t_{DVSH}/t_{DVEL}$ , and an address valid to end of write time of  $t_{\text{\tiny AVWH}} / t_{\text{\tiny AVSH}} / t_{\text{\tiny AVEL}}$  also must be provided for during the write operation. Hold times for address inputs and data inputs with respect to the disabling W/S/E edge transition must be a minimum of  $t_{\text{WHAX}}/t_{\text{SHAX}}/t_{\text{ELAX}}$  time and  $t_{WHDX}/t_{SHDX}/t_{ELDX}$  time, respectively. The minimum write cycle time is  $t_{AVAV}$ .

#### Radiation Characteristics

#### Total Ionizing Radiation Dose

The SRAM will meet all stated functional and electrical specifications over the entire operating temperature range after a total ionizing radiation dose of  $1x10^6$  rad(Si). All electrical and timing performance parameters will remain within specifications after rebound at  $V_{DD}=5.5$  V and  $T=125^{\circ}$ C extrapolated to ten years of operation. Total dose hardness is assured by wafer level testing of process monitor transistors and RAM product using 10 keV X-ray and Co60 radiation sources. Transistor gate threshold shift correlations have been made between 10 keV X-rays applied at a dose rate of  $1x10^5$  rad(Si)/min at  $T=25^{\circ}$ C and gamma rays (Cobalt 60 source) to ensure that wafer level X-ray testing is consistent with standard military radiation test environments.

#### Transient Pulse Ionizing Radiation

The SRAM is capable of writing, reading, and retaining stored data during and after exposure to a transient ionizing radiation pulse of  $\leq 50$  ns duration up to  $1\times10^9$  rad(Si)/s, when applied under recommended operating conditions. To ensure validity of all specified performance parameters before, during, and after radiation (timing degradation during transient pulse radiation is  $\leq 10\%$ ), stiffening capacitance can be placed on the package between the package (chip)  $V_{DD}$  and GND with the inductance between the package (chip) and stiffening capacitance kept to a minimum. If there are no operate-through or valid stored data requirements, typical de-coupling capacitors should be mounted on the circuit board as close as possible to each device.

The SRAM will meet any functional or electrical specification after exposure to a radiation pulse of  $\leq$  50 ns duration up to  $1x10^{12}$  rad(Si)/s, when applied under recommended operating conditions. Note that the current conducted during the pulse by the RAM inputs, outputs, and power supply may significantly exceed the normal operating levels. The application design must accommodate these effects.

#### **Neutron Radiation**

The SRAM will meet any functional or timing specification after a total neutron fluence of up to 1x10<sup>14</sup> cm<sup>-2</sup> applied under recommended operating or storage conditions. This assumes an equivalent neutron energy of 1 MeV.

#### Soft Error Rate

The SRAM has a soft error rate (SER) performance of <1x10<sup>-11</sup> upsets/bit-day, under recommended operating conditions. This hardness level is defined by the Adams 90% worst case cosmic ray environment.

#### Latchup

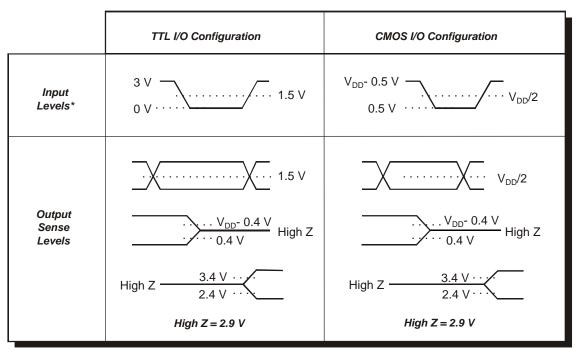
The SRAM will not latch up due to any of the above radiation exposure conditions when applied under recommended operating conditions.

## Radiation Hardness Ratings (1),(2)

Symbol	Characteristics	Conditions	Minimum	Maximum	Units
RTD	Total Dose	MIL-STD-883, TM 1019.5 Condition A	1E + 06		rad(Si)
RPRU	Prompt Dose Upset	20 - 50 ns Pulse Width $T_{case} = 25^{\circ}C$ and 125 $^{\circ}C$	1E + 09		rad(Si)/s
RS	Survivability	20 - 50 ns Pulse Width T <sub>case</sub> = 125°C	1E + 12		rad(Si)/s
SEU1	Single Event Upset(3)	-55°C ≤ T <sub>case</sub> ≤ 80°C		1E - 11	Upsets/Bit-Day
SEU2	Single Event Upset (3)	-55°C ≤ T <sub>case</sub> ≤ 125°C		1E - 10	Upsets/Bit-Day
RNF	Neutron Fluence		1E + 14		N/cm <sup>2</sup>
SEL	Single Event Induced Latchup	$-55^{\circ}\text{C} \le \text{T}_{\text{case}} \le 125^{\circ}\text{C}$ $\text{V}_{\text{DD}} = 5.5 \text{ V}$			Immune (4)

#### Notes:

- 1) Measured at room temperature unless otherwise stated. Verification test per TRB approved test plan.
- 2) Device electrical characteristics are guaranteed for post irradiation levels at 25°C.
- 3) 90% worst case particle environment, geosynchronous orbit, 0.025" of aluminum shielding. Specification set using the CREME code upset rate calculation method with a 2 µm epi thickness.
- 4) Immune for LET £ 120 MeV/mg/cm<sup>2</sup>.



\*Input rise and fall times <5 ns

#### Radiation Hardness Assurance

BAE SYSTEMS provides a superior quality level of radiation hardness assurance for our products. The excellent product quality is sustained via the use of our qualified QML operation which requires process control with statistical process control, radiation hardness assurance procedures and a rigid computer controlled manufacturing operation monitoring and tracking system.

The BAE SYSTEMS technology is built with resistance to radiation effects. Our product is designed to exhibit < 1e<sup>-11</sup> fails/bit-day in a 90% worst case geosynchronous orbit under worst case operating conditions. Total dose hardness is assured by irradiating test structures on every lot and total dose exposure with Cobalt 60 testing performed quarterly on TCI lots to assure the product is meeting the QML radiation hardness requirements.

#### Screening Levels

BAE SYSTEMS has two QML screen levels (Q and V) to meet full compliant space applications. For limited performance and evaluation situations, BAE SYSTEMS offers an engineering screen level.

#### Reliability

BAE SYSTEMS' reliability starts with an overall product assurance system that utilizes a quality system involving all employees including operators, process engineers and product assurance personnel. An extensive wafer lot acceptance methodology, using in-line electrical data as well as physical data, assures product quality prior to assembly. A continuous reliability monitoring program evaluates every lot at the wafer level, utilizing test structures as well as product testing. Test structures are placed on every wafer, allowing correlation and checks within-wafer, wafer-to-wafer, and from lot-to-lot.

Reliability attributes of the CMOS process are characterized by testing both irradiated and non-irradiated test structures. The evaluations allow design model and process changes to be incorporated for specific failure mechanisms, i.e., hot carriers, electromigration, and time dependent dielectric breakdown. These enhancements to the operation create a more reliable product.

The process reliability is further enhanced by accelerated dynamic life tests of both irradiated and non-irradiated test structures. Screening and testing procedures from the customer are followed to qualify the product.

A final periodic verification of the quality and reliability of the product is validated by a TCI (Technology Conformance Inspection).

Flour	QML	Level	Comments
Flow	Q	V	Comments
Wafer Lot Acceptance	Χ	Х	Alternate Method Used
Serialization	Χ	Х	Die Traceability
Destructive Bond Pull	Sample	Sample	
Internal Visual	Χ	X	MIL-STD-883, TM 2010
Temperature Cycle	Χ	Х	
Constant Acceleration	Х	Х	
PIND	Χ	Х	
Radiography		Х	
Electrical Test	Χ	X	
Dynamic Burn-In	Χ	Х	
Electrical Test		Х	
Static Burn-In		Х	5.5 V, 125°C, 144 Hours
Final Electrical	Χ	Х	Meets Group A
PDA	Χ	Х	< 5% Fallout
Fine and Gross Leak	Χ	X	
External Visual	Х	Х	MIL-STD-883, TM 2009

#### **Burn-In Circuit**

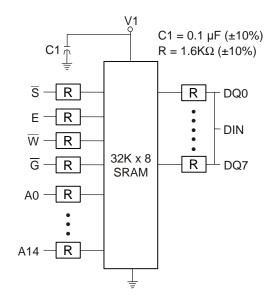
#### Stress Methodology

There are two methods of burn-in defined. For "Static" burn-in, all possible addresses are written with a logic "1" for half of the burn-in duration and a logic "0" for the remaining half. For "Dynamic" burn-in, all possible addresses are written with alternating high and low data.

All I/O pins specified in the static and dynamic burn-in pin lists are driven through individual series resistors (1.6K  $\Omega$  ±10%). The burn-in circuit diagram is shown at right.

#### Voltage Levels

- Vin(0): 0.0 V to + 0.4 V
  - V<sub>IL</sub> = Low level for all programmed signals
- •Vin(1): + 5.4 V to + 6.0 V
  - V<sub>IH</sub> = High level for all programmed signals
- V1: + 5.5 V (-0% / +10%)
  - All V<sub>DD</sub> pins are tied to this level
- •Vsx: Float or GND
  - All GND pins are tied to this level



# Pin Listing The dynamic burn-in pin listing is shown at right. F = square wave,

100 KHz to 1.0 MHz.

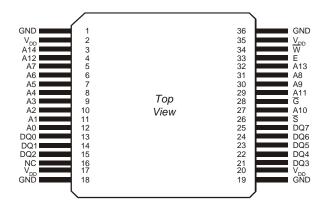
Input	Signal	Input	Signal	Input	Signal	Input	Signal
A0	F/2	A5	F/64	A10	F/2048	W	F/65536
A1	F/4	A6	F/128	A11	F/4096	D <sub>IN</sub>	F/131072
A2	F/8	A7	F/256	A12	F/8192	S	F
A3	F/16	A8	F/512	A13	F/16384	G	V <sub>IL</sub>
A4	F/32	A9	F/1024	A14	F/32768	Ē	V <sub>IH</sub>

#### **Packaging**

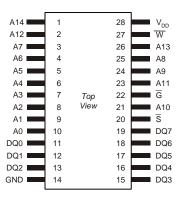
The 32K x 8 SRAM is offered in a custom 36-lead FP, 36-lead FPP or standard 28-lead DIP. All packages are constructed of multilayer ceramic ( ${\rm Al_2O_3}$ ) and feature internal power and ground planes. The FP also features a non-conductive ceramic tie bar on the lead frame. The purpose of the tie bar is to allow electrical testing of the device, while preserving the lead integrity during shipping and handling, up to the point of lead forming and insertion.

Optional capacitors can be mounted to the package to maximize supply noise decoupling and increase board packing density. These capacitors attach directly to the internal package power and ground planes. This design minimizes resistance and inductance of the bond wire and package, both of which are critical in a transient radiation environment. All NC pins must be connected to either V<sub>DD</sub>, GND or an active driver to prevent charge build up in the radiation environment. (NC = no connect.)

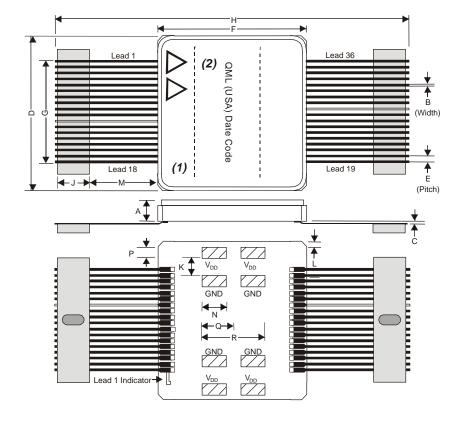
#### 36-Lead Flat Pack Pinout



#### 28-Lead DIP Pinout



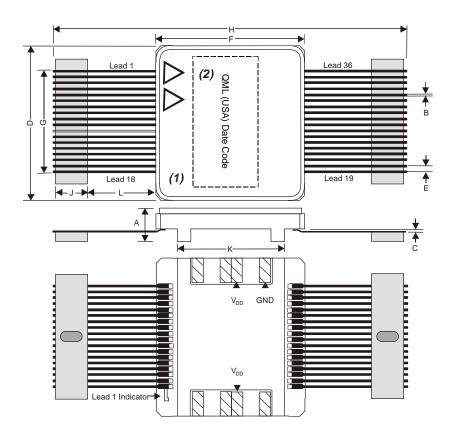
#### 36-Lead Flat Pack



A=.085 ± .010	J=.135
B=.008 ± .002	K=.080
C=.013 ± .004	L=.020
D=.650 ± .010	M=.285
F=.025 + .002	N=.100
F=.630 ± .007	P=.040
G=.425 ± .004	Q=.130
H=1.490	R=.260

#### Notes:

- 1) Part mark per device specification.
- 2) "QML" may not be required per device specification.
- 3) Dimensions are in inches.
- 4) Lead width: .008 ± .002.
- 5) Lead height: .006 ± .002.
- 6) Unless otherwise specified, all tolerances are ± .005".



B=.008 ± .002
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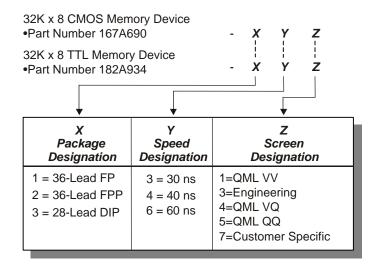
#### Notes:

- 1) Part mark per device specification.
- 2) "QML" may not be required per device specification.
- 3) Dimensions are in inches.
- 4) Lead width: .008 ± .002.
- 5) Lead height: .006 ± .002.
- 6) Unless otherwise specified, all tolerances are ± .005".

#### 28-Lead DIP

For 28-Lead DIP description, see MIL-STD-1835, type CDIP2-T28, configuration C, dimensions D-10.

## Ordering Information



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